L Number	Hits	Search Text	DB	Time stamp
18	2	("5415754").PN.	USPAT;	2003/02/28 09:49
			EPO; JPO;	
			DERWENT	
-	1647	magnetic adj shunt	USPAT;	2003/02/28 08:56
			EPO; JPO;	
			DERWENT	
•	19	(magnetic adj shunt) and 250/\$.ccls.	USPAT;	2003/02/26 13:01
			EPO; JPO;	
			DERWENT	
-	92	(magnetic adj shunt) and optic\$5	USPAT;	2003/02/28 09:49
			EPO; JPO;	
			DERWENT	
-	902	shunt and 250/\$.ccls.	USPAT;	2003/02/26 13:02
			EPO; JPO;	2005,02,2015.0.
			DERWENT	
-	224	(shunt and 250/\$.ccls.) and magnetic	USPAT;	2003/02/26 13:02
	224	(Shuff and 250 p.ccis.) and magnetic	1 '	2003/02/20 13:02
			EPO; JPO;	
	1,12	((-h	DERWENT	2002/20/20/20
•	113	((shunt and 250/\$.ccls.) and magnetic) and (stage wafer)	USPAT;	2003/02/26 13:09
			EPO; JPO;	
			DERWENT	
•	208	magnetic adj shunt same (stage hold\$4 wafer substrate base)	USPAT;	2003/02/26 14:43
			EPO; JPO;	
			DERWENT	
-	14	(magnetic adj shunt same (stage hold\$4 wafer substrate base) same	USPAT;	2003/02/26 14:45
		(mov\$4 translat\$4 position\$4)) and optic\$4	EPO; JPO;	
		(mary manusary passages)) and space .	DERWENT	
_	106	magnetic adj shunt same (stage hold\$4 wafer substrate base) same	USPAT;	2003/02/26 15:29
-	100	(mov\$4 translat\$4 position\$4)	1	2003/02/20 13.2
		(110v94 tratistat94 position94)	EPO; JPO;	
	66272	magnetic come (stage helded wafer substrate here) come (maye)	DERWENT	2002/02/06 15 21
-	66272	magnetic same (stage hold\$4 wafer substrate base) same (mov\$4	USPAT;	2003/02/26 15:31
		translat\$4 position\$4)	EPO; JPO;	
			DERWENT	
•	43181	magnetic same (mov\$4 translat\$4 position\$4) with (stage hold\$4 wafer	USPAT;	2003/02/26 15:41
		substrate base)	EPO; JPO;	
			DERWENT	
-	1216	(magnetic same (mov\$4 translat\$4 position\$4) with (stage hold\$4 wafer	USPAT;	2003/02/26 15:42
		substrate base)) and permeable	EPO; JPO;	
			DERWENT	
	337	((magnetic same (mov\$4 translat\$4 position\$4) with (stage hold\$4 wafer	USPAT;	2003/02/26 15:47
		substrate base) and permeable) and (optic\$ illuminat\$5)	EPO; JPO;	
		(about the state of the state o	DERWENT	
	43	(((magnetic same (mov\$4 translat\$4 position\$4) with (stage hold\$4 wafer	USPAT;	2003/02/26 16:13
_	4.7	substrate base) and permeable) and (optic\$ illuminat\$5)) and 250/\$.ccls.	EPO; JPO;	2005/02/20 10.1
		substance base) , and permisable) and (opines munimacs)), and 200/\$.008.	DERWENT	
	18	(("4310764") or ("4465934") or ("4607167") or ("4628466") or	USPAT;	2003/02/26 16:19
•	18		1	2003/02/26 16:18
		("4866280") or ("4985634") or ("5446722") or ("6285097")).PN.	EPO; JPO;	
	_		DERWENT	
	8	(("4310764") or ("4465934") or ("4607167") or ("4628466") or	USPAT	2003/02/26 16:18
		("4866280") or ("4985634") or ("5446722") or ("6285097")).PN.		
-	8) (()	USPAT;	2003/02/27 08:0
		("4866280") or ("4985634") or ("5446722") or ("6285097")).PN.) and	EPO; JPO;	
		magnet\$4	DERWENT	
	3	(("4444643") or ("4714536") or ("5320728")).PN.	USPAT	2003/02/27 08:08
-	310		USPAT;	2003/02/27 08:09
]		EPO; JPO;	
			DERWENT	
-	2140005	(magnetic adj shunt.clm.) and stage wafer base	USPAT;	2003/02/27 08:0
	3148085	(magnetic auf shunt.cini.) and stage water base		2003/02/2/ 00:0
			EPO; JPO;	
			DERWENT	2000/05/25 25 3
-	141	(magnetic adj shunt.clm.) and (stage wafer base)	USPAT;	2003/02/27 08 09
			EPO; JPO;	
	§	1	DERWENT	